

REMARKS

Applicants thank Examiner Chen for the helpful and courteous discussion of December 13, 2005. During the discussion Applicant's representative argued that the prior art relied upon by the Office in the Office Action of October 26, 2005 does not disclose a substrate covered with one or more layers of an organopolysilicon polymer.

The presently claimed invention is drawn to a chemical mechanical planarization stopper film. The film of present Claim 1 is present on the surface of a substrate. The substrate of Claim 1 may be, for example, a wafer (see new dependent Claim 12). The wafer of Claim 12 may be one or more of the materials now recited in Claim 13.

Applicants submit that the prior art relied upon by the Office, Buvat (U.S. 6,703,519), does not describe a film of an organosilicon polymer. Further, Buvat does not disclose a chemical mechanical planarization stopper film that is present on the surface of a substrate. Buvat may describe hardened products obtained by heat treating the prior art materials. However, the prior art hardened product is used as a matrix in a composite (column 1, lines 12-13; column 11, lines 34-36; column 11, lines 41-45; and column 13, lines 33-36).

Applicants draw the Office's attention to new dependent Claim 15, wherein the chemical mechanical planarization stopper film of Claim 1 is required to "consist of" the organosilicon polymer. Because new dependent Claim 15 contains the transitional phrase "consists of", there are no other materials present in the film other than the organosilicon polymer. Applicants submit that a film that consists of an organosilicon polymer is different from a matrix composition that contains other materials.

Applicants submit that amended Claim 1 is novel and not obvious in view of Buvat on the grounds that Buvat does not disclose or suggest a film of an organosilicon polymer that is present on the surface of a substrate and which is a chemical mechanical planarization

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stopper film. Applicants request the withdrawal of the rejection and the passage of all now-pending claims to allowance.

REQUEST FOR REJOINDER

Upon the Office's determination that the chemical mechanical planarization stopper film according to Claim 1 is allowable, Applicants respectfully request rejoinder and allowance of the non-elected claims amended herein to recite a chemical mechanical planarization stopper film or a chemical mechanical planarization stopper composition.

Further to the Restriction Requirement, the Office states the Applicants' response filed on October 5, 2005 was made without traverse. This is not correct. Applicants explicitly traversed the Restriction Requirement as shown by the arguments on pages 2 and 3 of the October 5 response, and the statement on page 1 which states that the election is made with traverse.

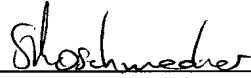
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